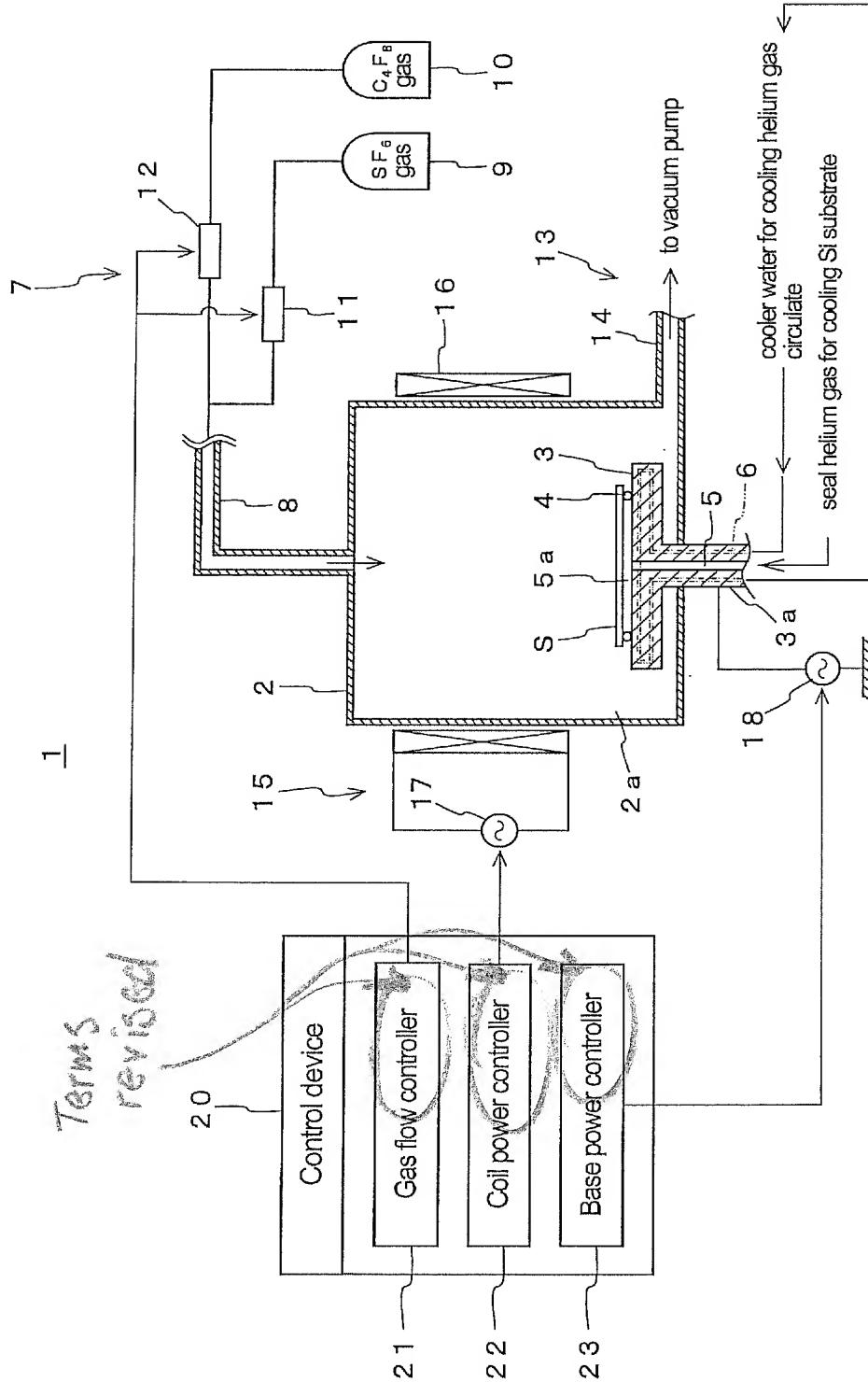


Fig. 1



Reference
numerals corrected

Fig. 3

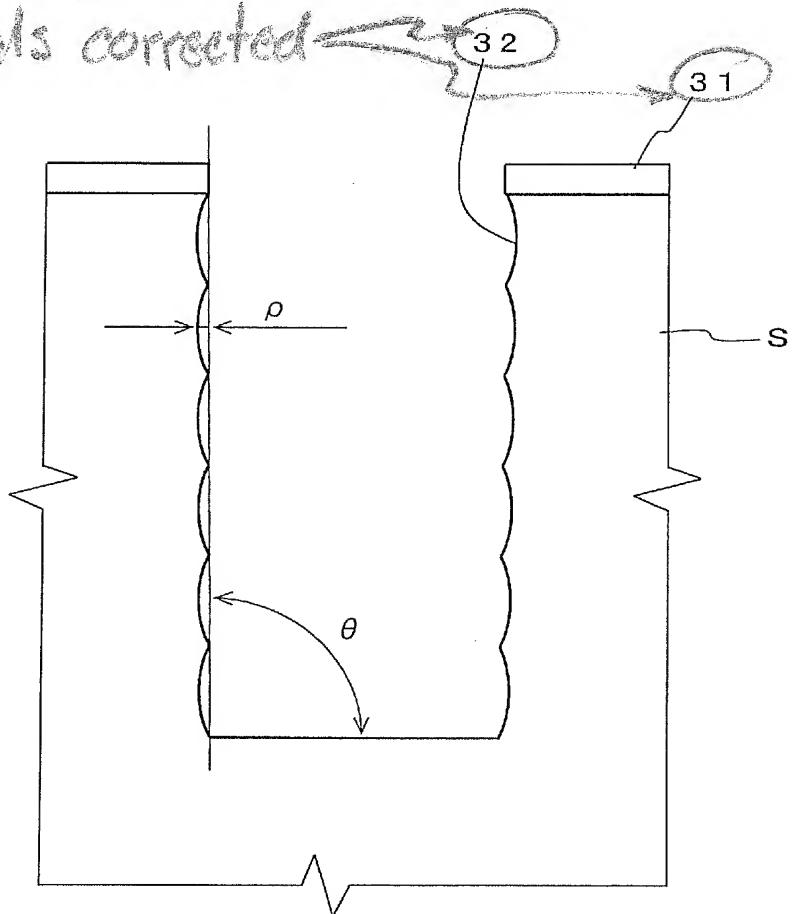


Fig. 4

	Embodiment	Comparative Example
Etching rate ($\mu\text{m}/\text{min}$)	3.7	3.4
Mask selection ratio	140	104
Unevenness ρ (nm)	160	250
Hole sidewall angle (degrees)	90.2	90.5

Missing units added